

SFB 917  
**Nanoswitches**

JARA|FIT

JÜLICH  
FORSCHUNGSZENTRUM

# Redox-based switching mechanisms in memristive devices studied by synchrotron-based spectromicroscopy

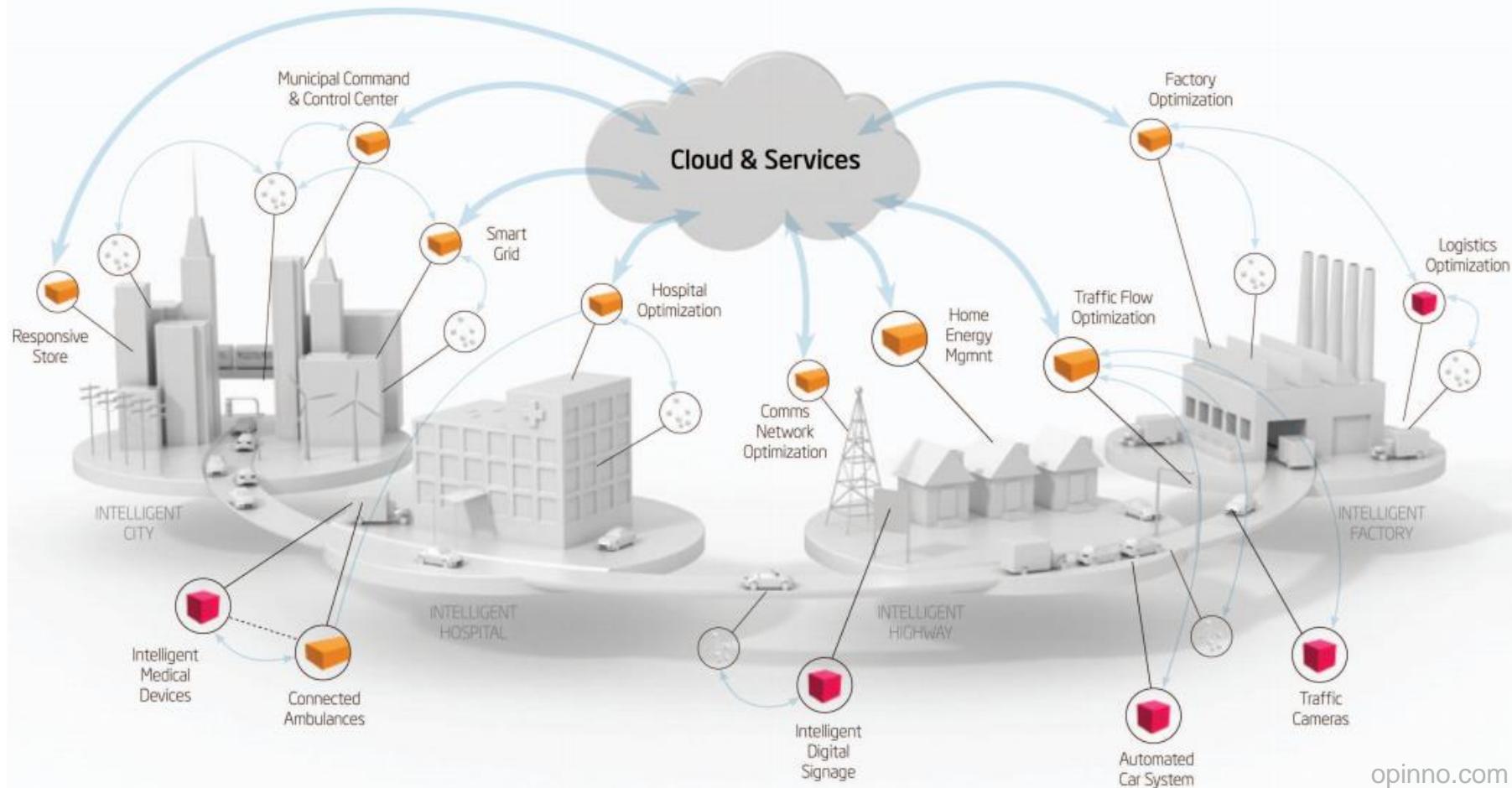
C. Bäumer<sup>1</sup>, C. Schmitz<sup>2</sup>, C. M. Schneider<sup>2</sup>,  
R. Waser<sup>1,3</sup> & R. Dittmann<sup>1</sup>

<sup>1</sup>Peter-Grünberg Institut (PGI-7), Forschungszentrum Jülich GmbH, Germany

<sup>2</sup>Peter-Grünberg Institut (PGI-6), Forschungszentrum Jülich GmbH, Germany

<sup>3</sup>Institute of Electronic Materials (IWE-2), RWTH Aachen, Germany

- 1. Motivation:** Memristive devices for nonvolatile memory
  
- 2. *Operando* spectromicroscopy:**  
Comprehensive understanding of memristive processes: oxygen vacancy motion
  
- 3. Post mortem spectromicroscopy:**  
Design rules to prevent retention failure
  
- 4. Beam-sample interaction**
  
- 5. Conclusion**



opinno.com

Technological revolution requires new concepts in data storage and mobile computing

## Flash



<https://en.wikipedia.org/>

- non-volatile
- slow
- switching time:  $\mu\text{s}$
- high voltage required

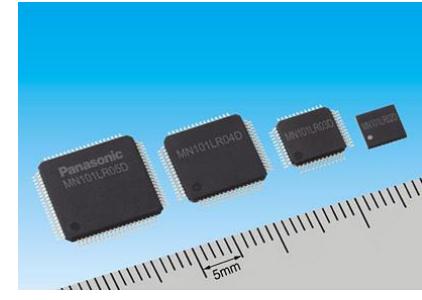
## DRAM



<https://en.wikipedia.org/>

- volatile
- fast
- switching time: ns
- refresh power and time

## ReRAM



<http://news.panasonic.com/>

- non-volatile
- fast
- switching time: ns
- **Complex mechanisms**

Kent, *Nat. Nanotech.* **10** (2015)

# Resistive Switching for non-volatile memory

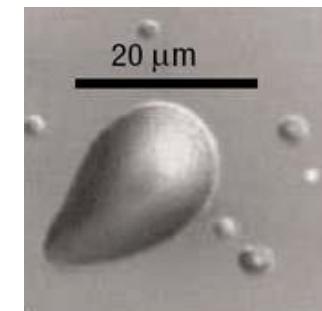
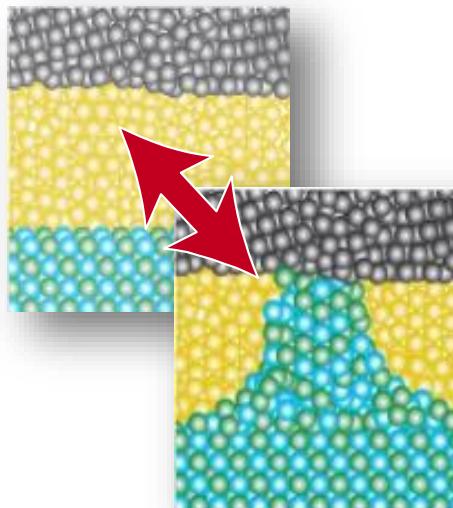
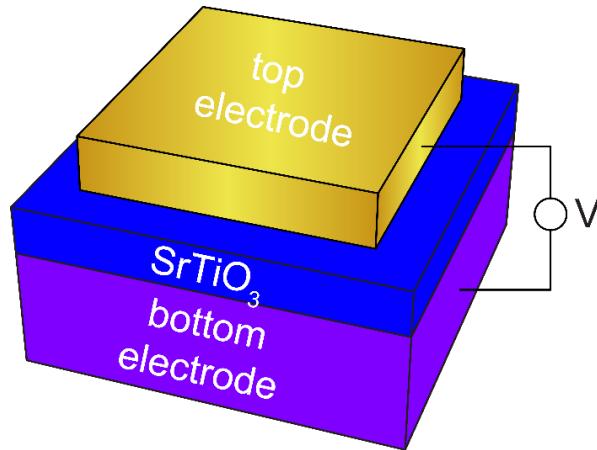
Szot *et al.*, Nat. Mater. **5** (2006)

Waser *et al.*, Nat. Mater. **6** (2007)

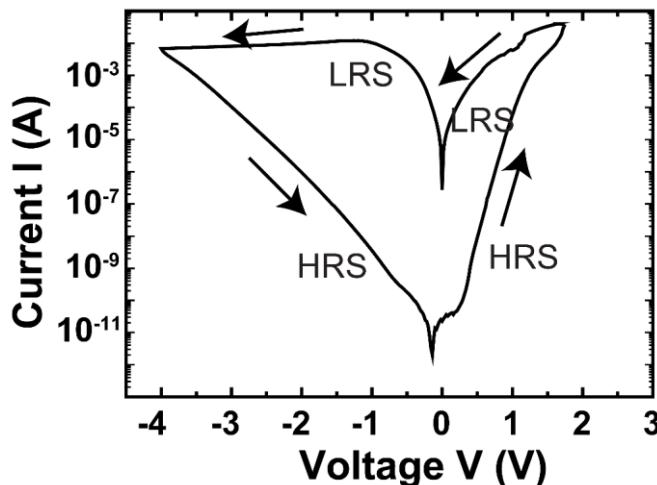
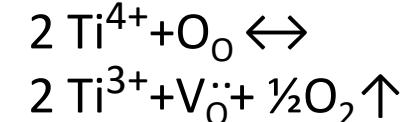
Waser *et al.*, Adv. Mater. **21** (2009)

Wong *et al.*, Proceedings of the IEEE **100** (2012)

Cooper *et al.*, Adv. Mater. (accepted, 2017)



Oxygen evolution  
underneath the anode:



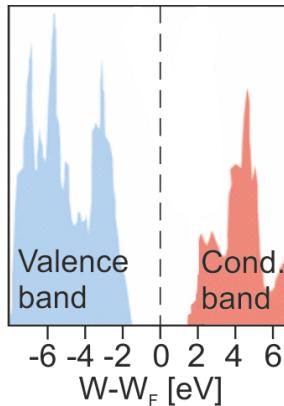
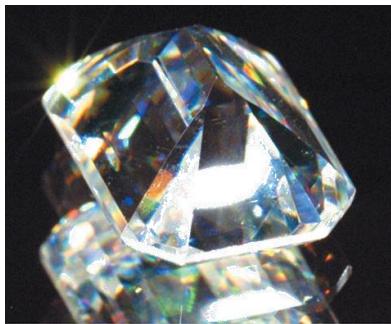
Baeumer *et al.*, Nat. Commun. **6** (2015)

- Oxygen vacancy generation and redistribution under applied field → local redox reaction
- Spatial confinement: filamentary switching
- ?
- ?
- ?
- **Spectromicroscopic quantification mandatory**

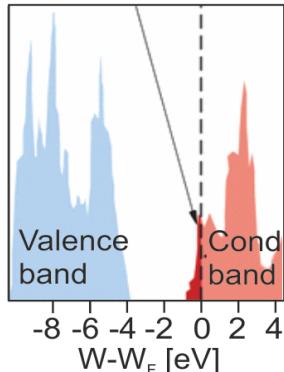
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Comprehensive understanding of memristive processes: oxygen vacancy motion
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# Model material of choice: SrTiO<sub>3</sub>

- Stoichiometric SrTiO<sub>3</sub>: transparent, insulating

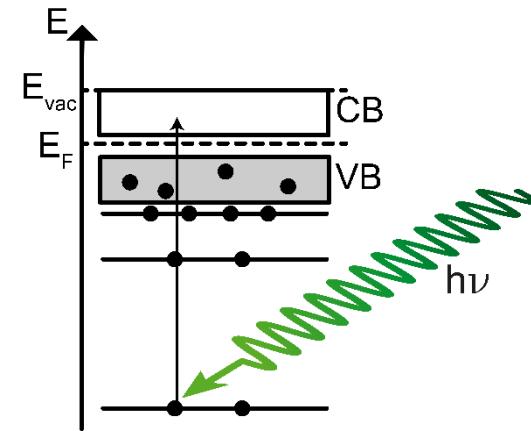


- Oxygen deficient SrTiO<sub>3-δ</sub>: opaque, conducting

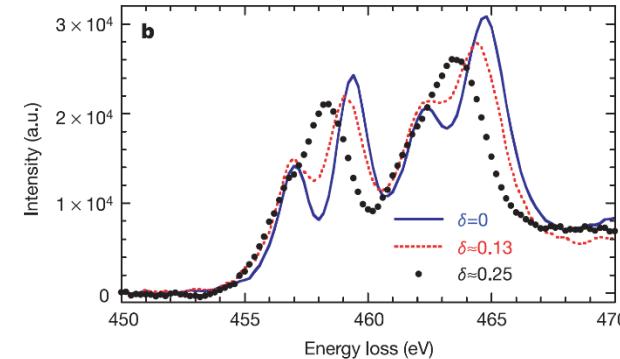


Waser, *Adv. Mater.* **21** (2009)

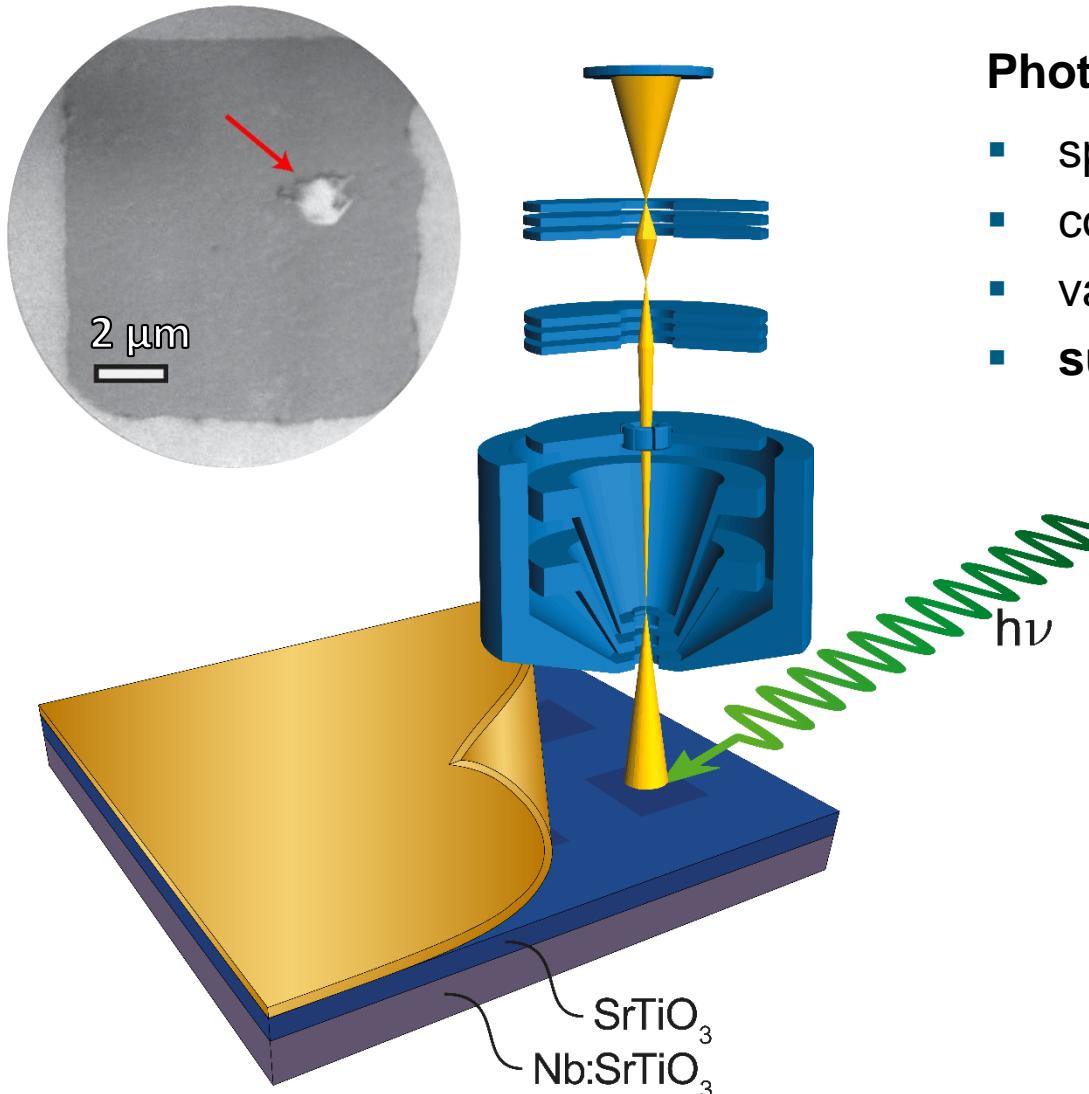
- X-ray absorption spectroscopy, EELS



- oxygen vacancies cause significant spectral changes

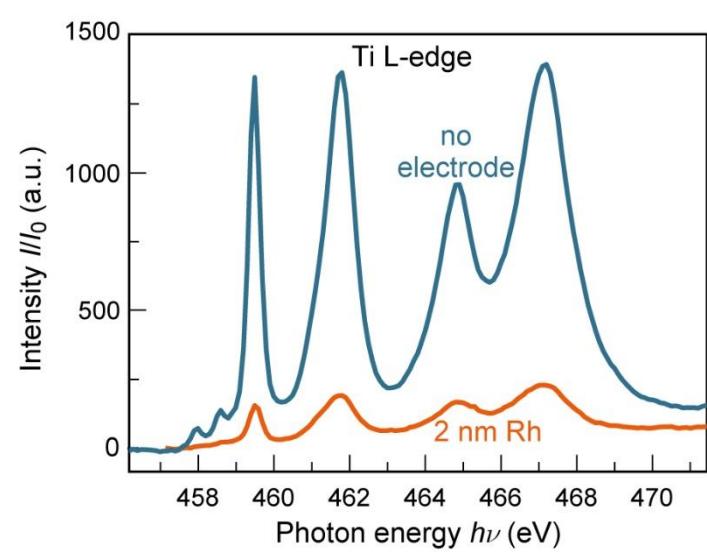


Muller, *Nature* **430** (2004)

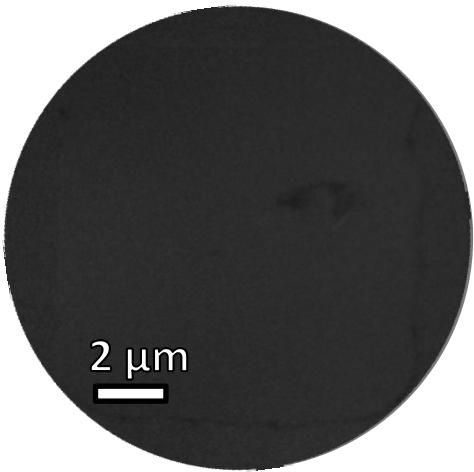


## Photoelectron emission microscopy

- spatially resolved XPS and XAS
- composition sensitive
- valence state sensitive
- **surface sensitive**

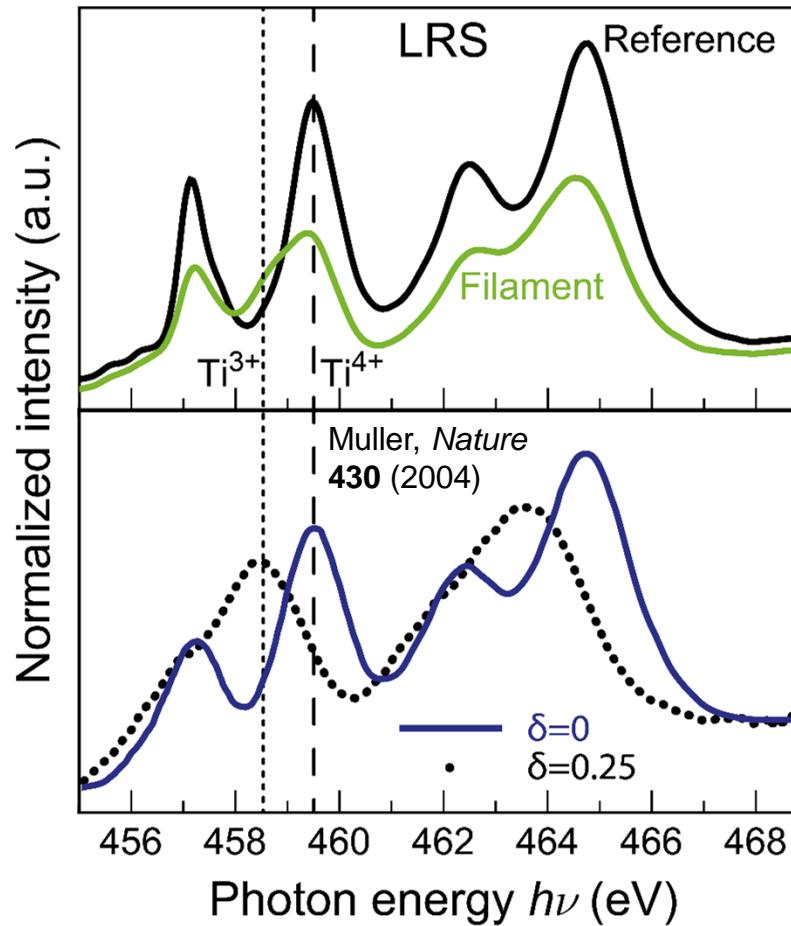


PEEM image stack

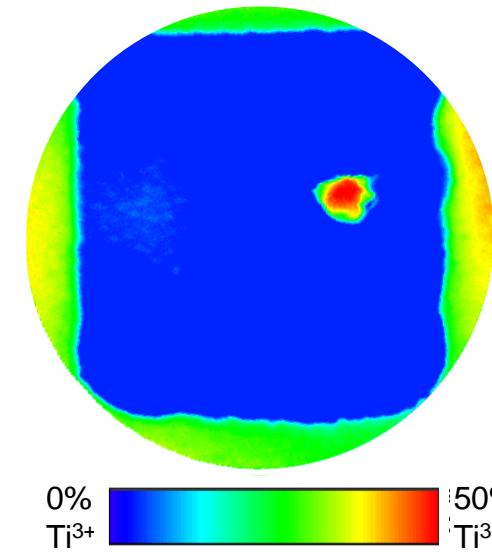


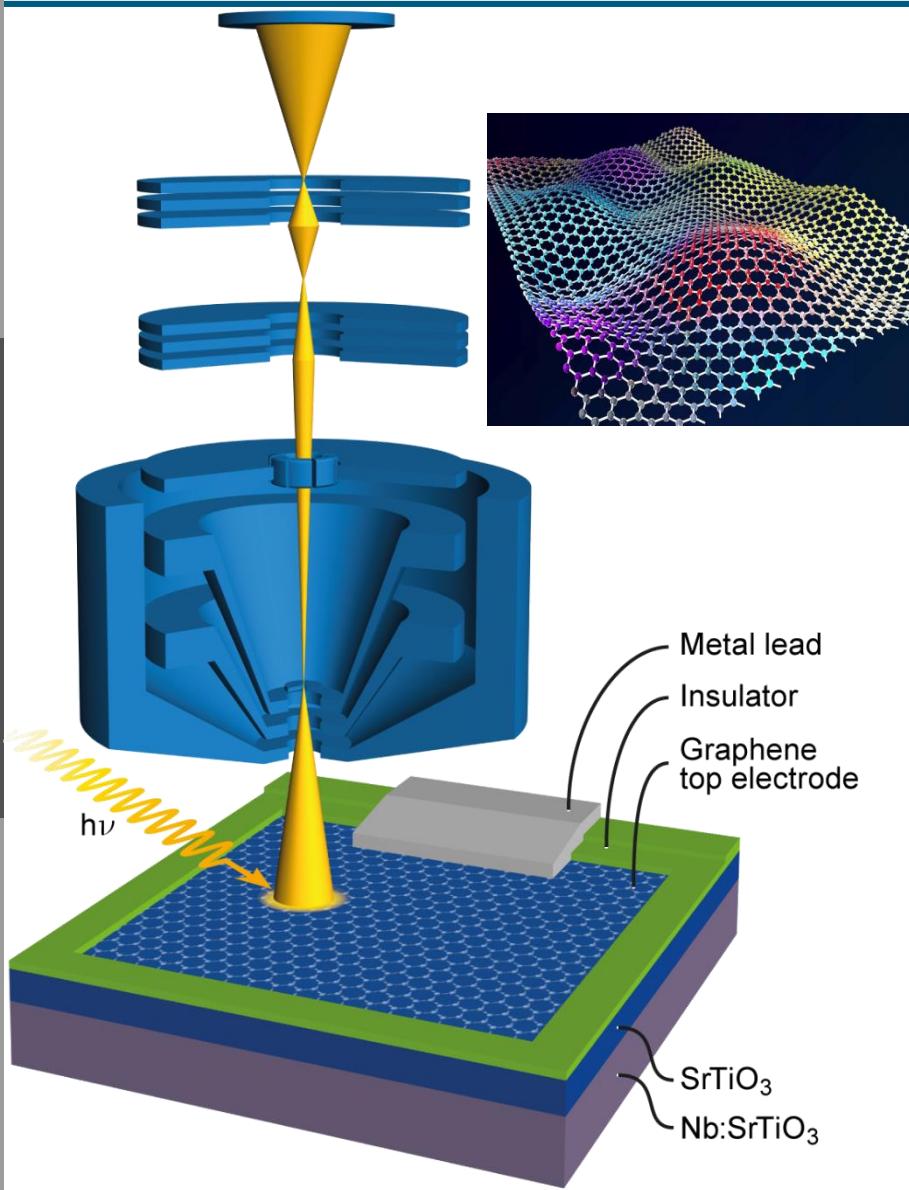
- Identification of switching filament
- LRS: Ti<sup>3+</sup> filament in Ti<sup>4+</sup> matrix
- ? Switching details

Ti L-edge spectra



False color map

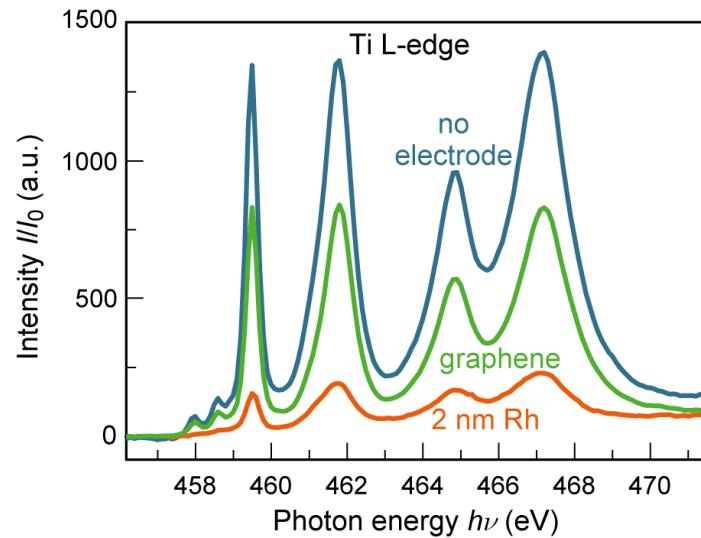




Baeumer et al., Nat. Commun. 7 (2016)

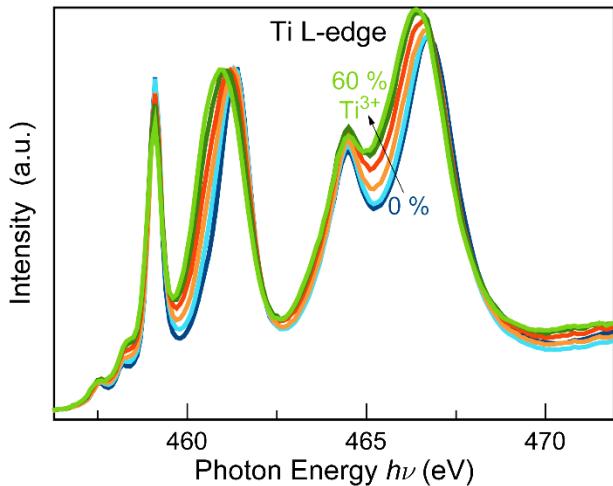
## Photoelectron emission microscopy

- surface sensitivity:  
need for ultra-thin electrode
- graphene is the ideal candidate
- excellent signal-to-noise ratio



graphene growth:  
S. Rogers, M. Shim, University of Illinois

# Spectroscopic fingerprint of valence changes

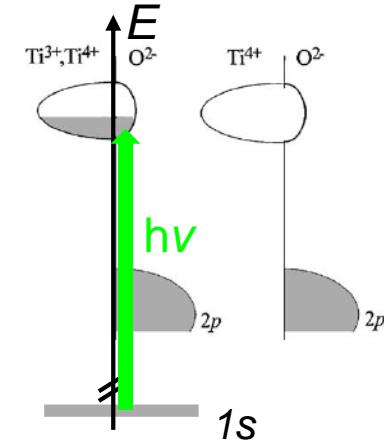
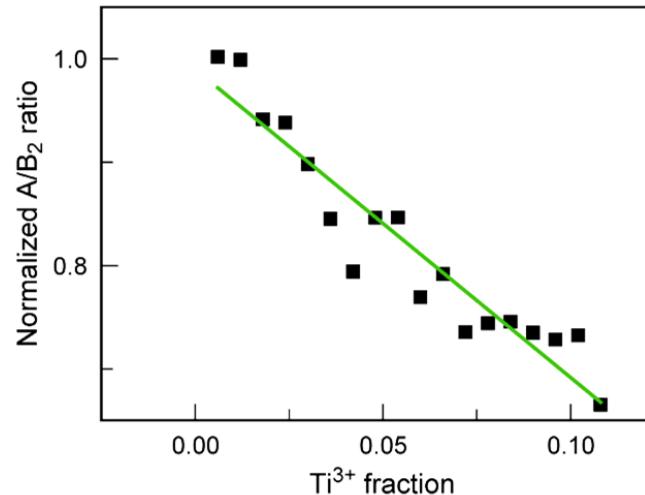
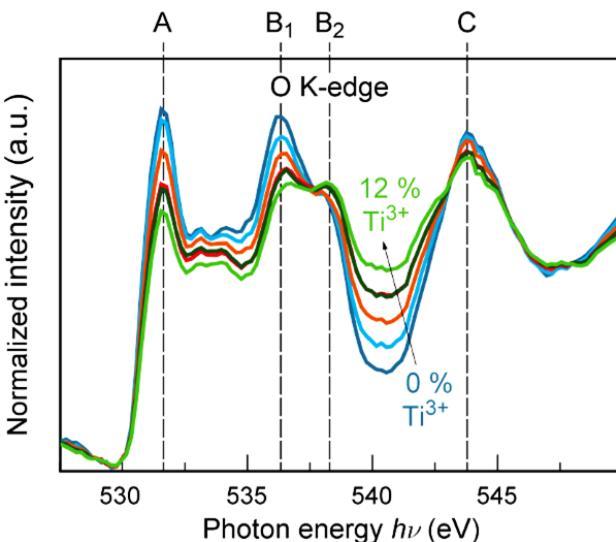


## Ti L edge

- Large changes: significant spectral changes
- Subtle changes: spectral features hard to detect

## O K edge

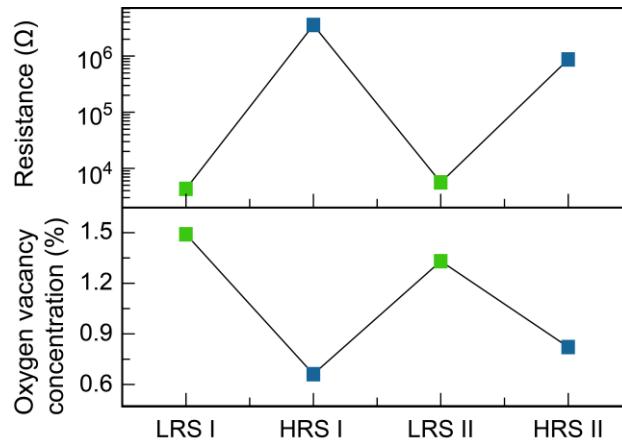
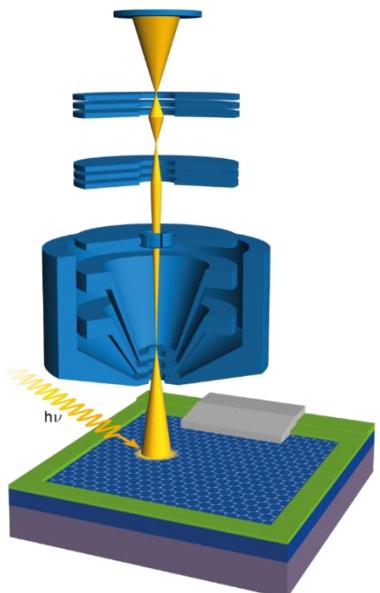
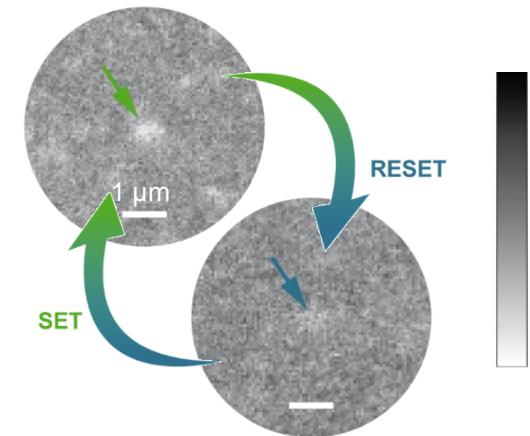
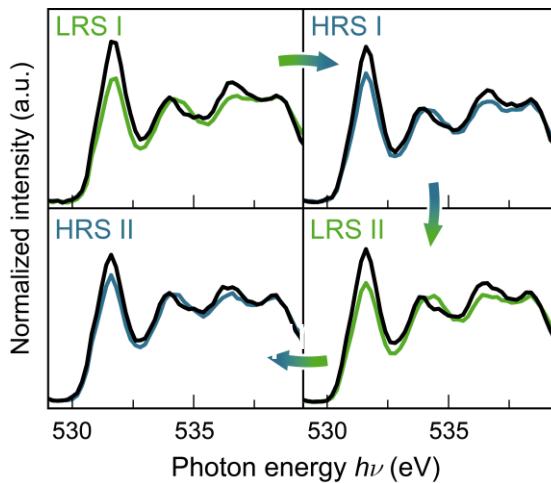
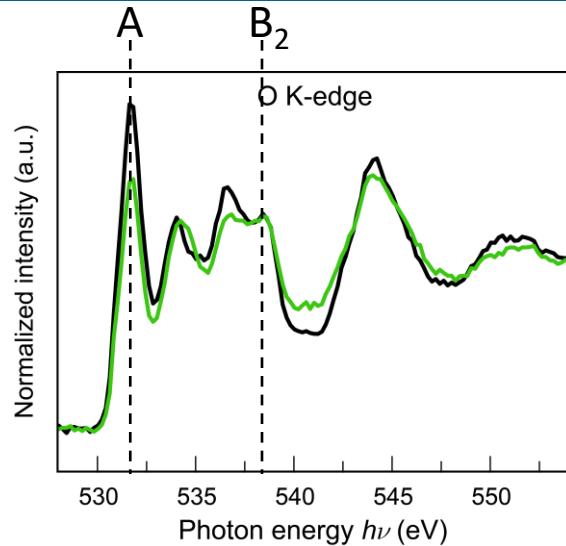
- Subtle changes: O K-edge very sensitive
- Direct measure for electrons in conduction band



Baeumer, *Nat. Commun.* **7** (2016), Abbate, *PRB* **46**, 4511 (1992)

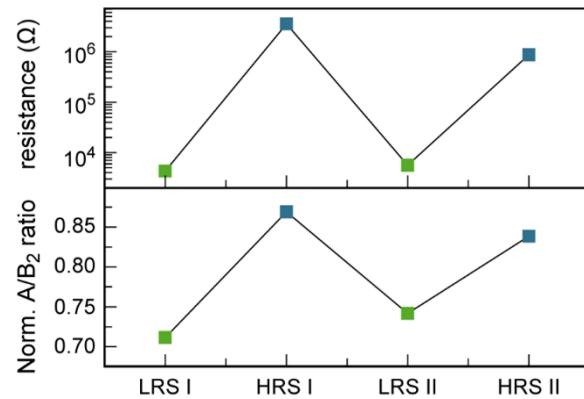
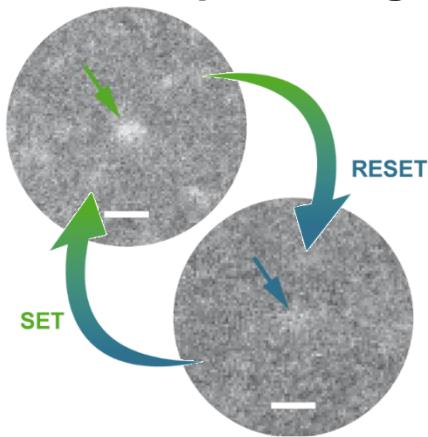
Sefat, *Solid State Chem.* **178** (2005)

# Quantifying oxygen vacancy variations

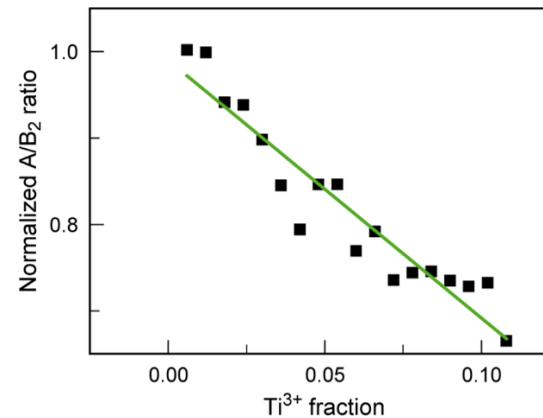


- Switching-induced modulation in oxygen vacancy concentration
- Variation by factor 2-3
- Agreement with resistance change
- Variation by  $10^2$ - $10^3$

## Spectroscopic change



## Comparison with calibration



	LRS	HRS
$N_{VO}$	$3.35 \times 10^{20} \text{ cm}^{-3}$	$7.5 \times 10^{20} \text{ cm}^{-3}$
$n$	$1.5 \times 10^{21} \text{ cm}^{-3}$	$6.7 \times 10^{20} \text{ cm}^{-3}$

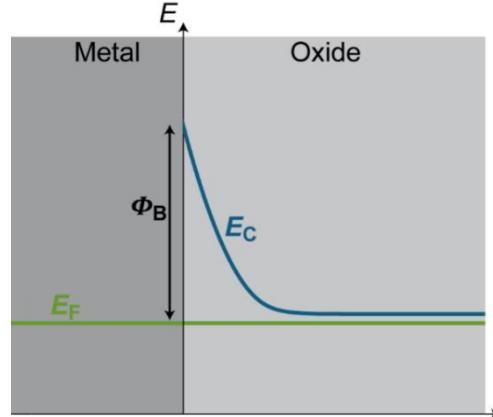


- ✓ Redox-induced carrier density modulations
- ✓ Variation by factor 2-3
- ✓ Agreement with resistance change
- ✓ Variation by  $10^2$ - $10^3$

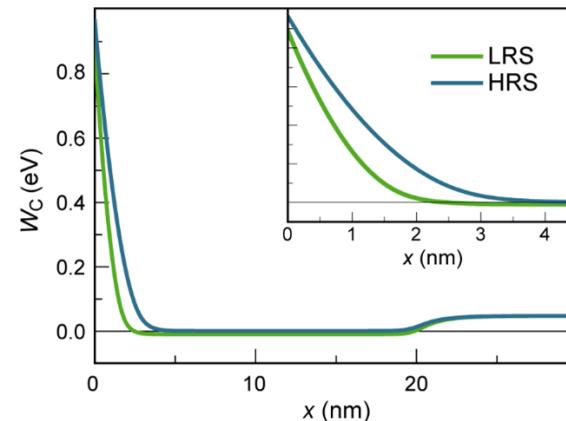
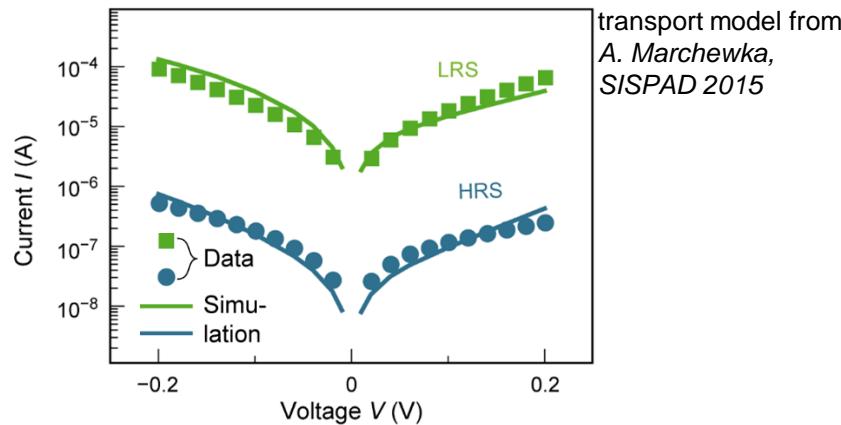
# Quantitative treatment of VCM switching

- experimental quantities:  
resistance + vacancy concentration
- understanding the device  
resistance: A Schottky barrier

	LRS	HRS
$N_{VO}$	$3.35 \times 10^{20} \text{ cm}^{-3}$	$7.5 \times 10^{20} \text{ cm}^{-3}$
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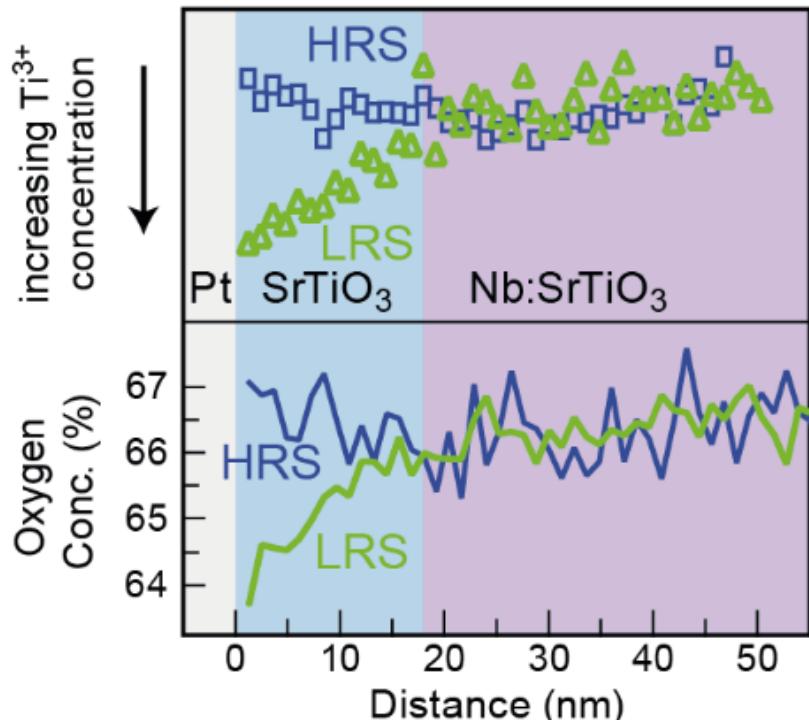
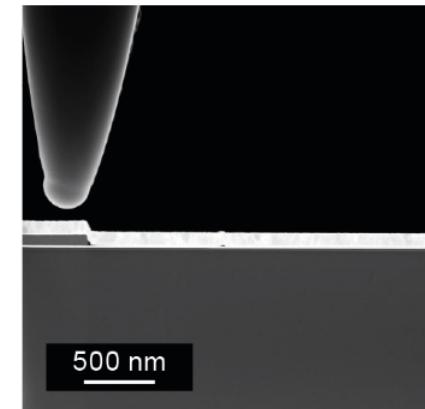
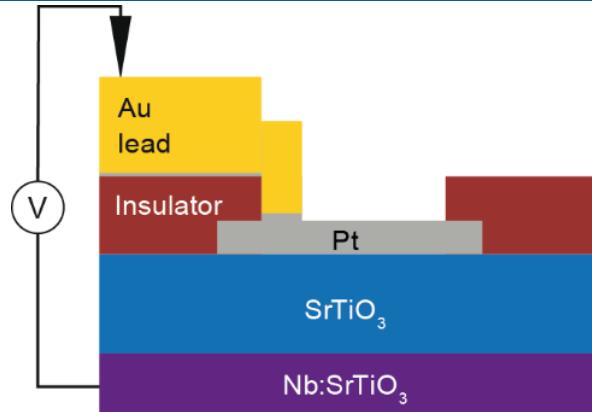
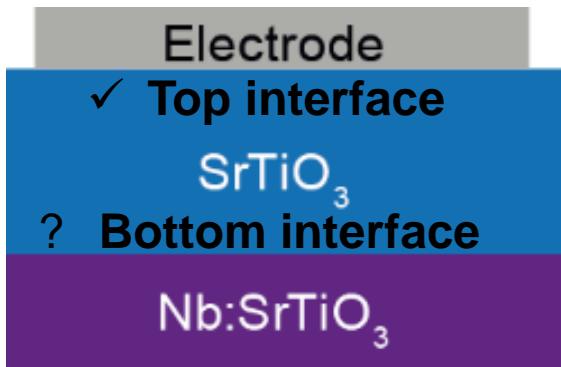


- transport model based on  
experimental quantities
- oxygen vacanciy variation causes  
Schottky barrier modification



Baeumer, Nat. Commun. 7 (2016). Simulation: A. Marchewka & S. Menzel, RWTH Aachen & FZJ

# TEM-based oxygen vacancy mapping



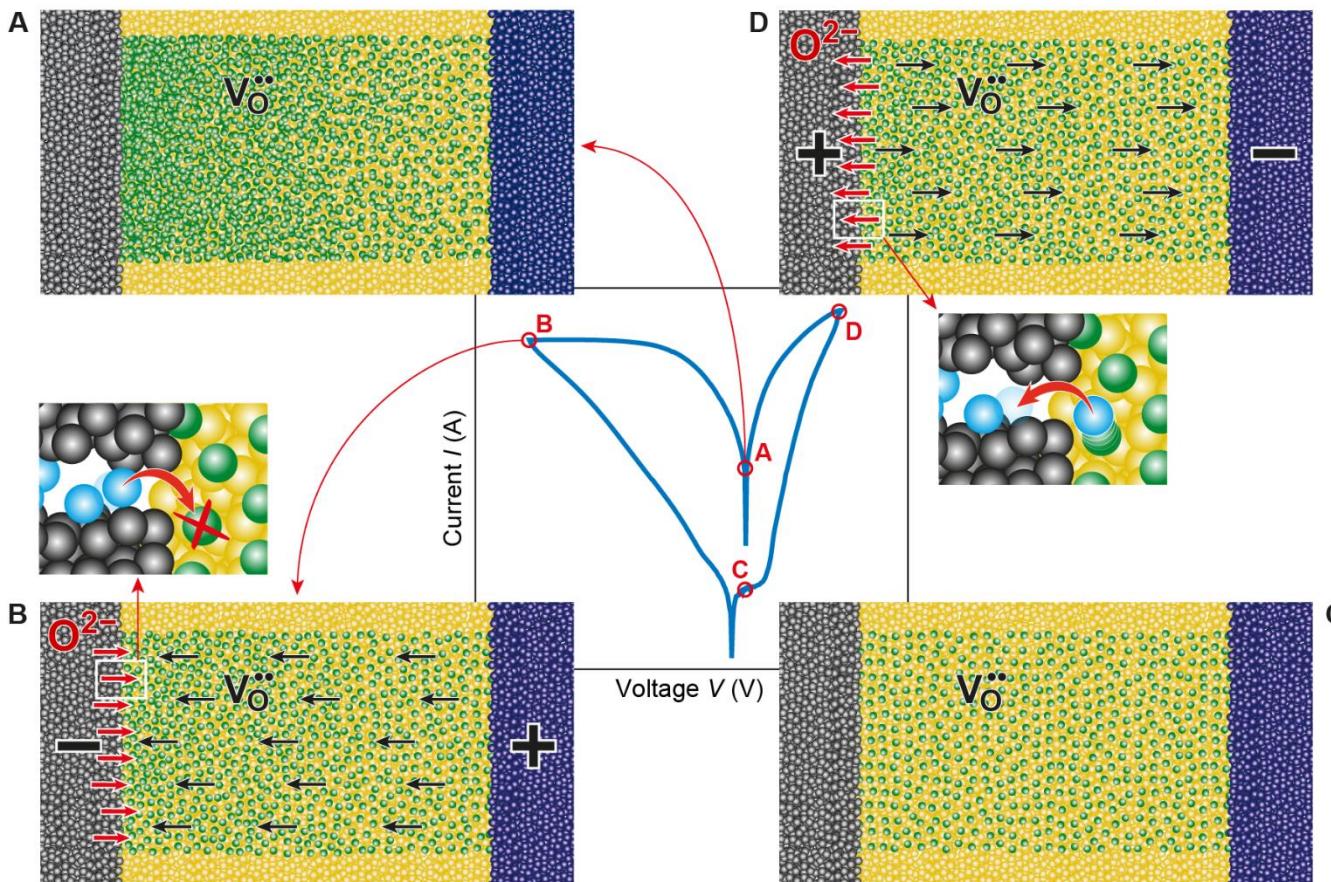
Cooper, Baeumer et al., Adv. Mater. (accepted, 2017)

- ✓ *In operando* TEM clarifies switching details
- ✓ Concentration variation only at top interface
- ✓ Agreement with PEEM data
- ✓ LRS: decrease of the total oxygen concentration in the film
- ✓ LRS:  $\text{Ti}^{3+}$  gradient
- ✓ HRS: Nearly stoichiometric  $\text{SrTiO}_3$

Oxygen evolution and reincorporation reaction:  $2\text{Ti}^{4+} + \text{O}_\text{o} \leftrightarrow 2\text{Ti}^{3+} + \text{V}_\text{o}^{\cdot\cdot} + \frac{1}{2}\text{O}_2 \uparrow$

Set: left to right

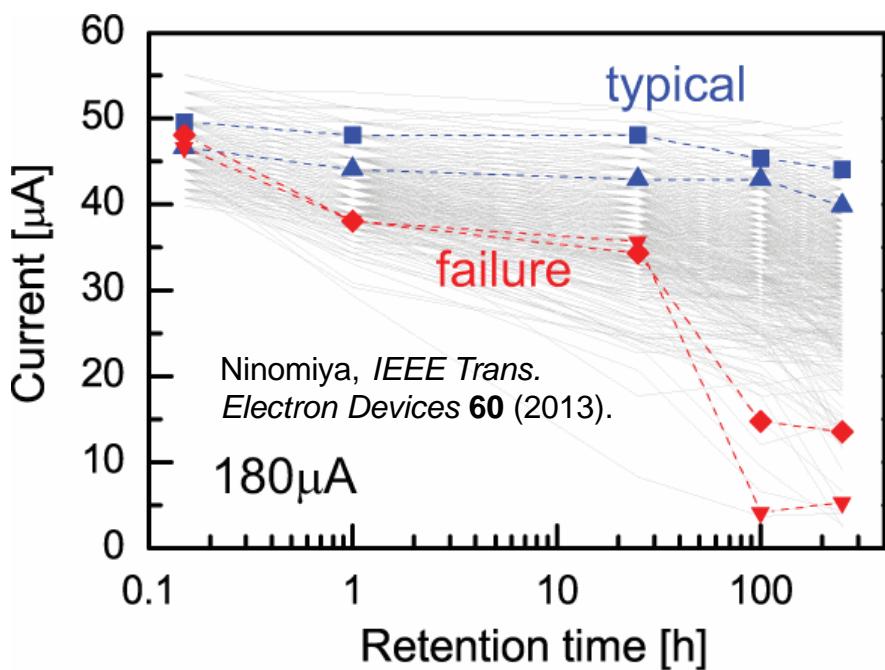
Reset: right to left



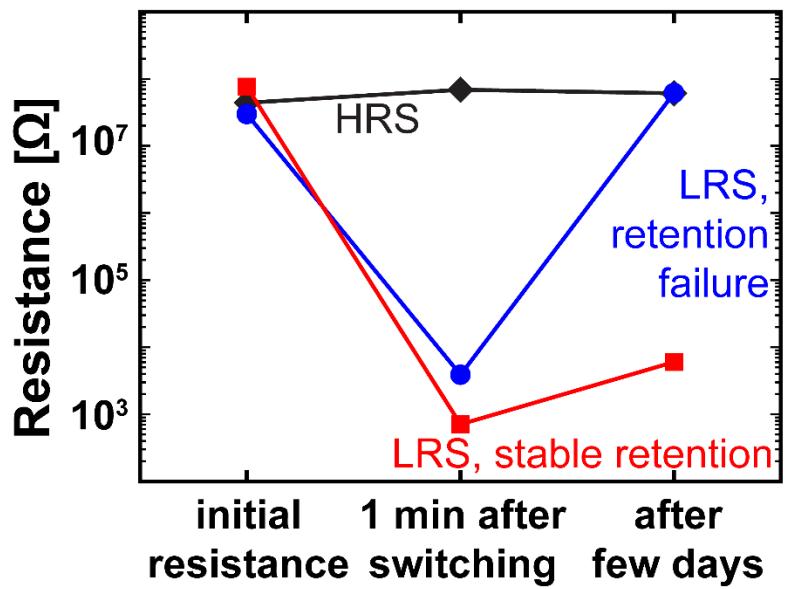
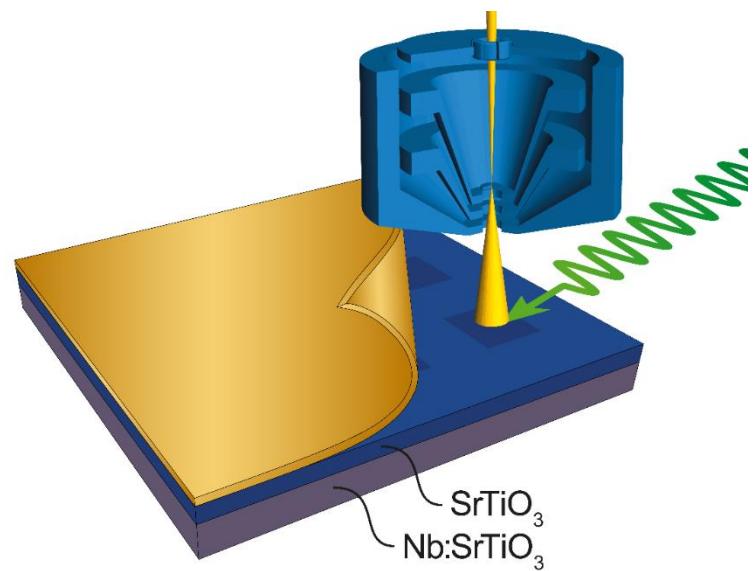
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# Nonvolatile memory: Data retention

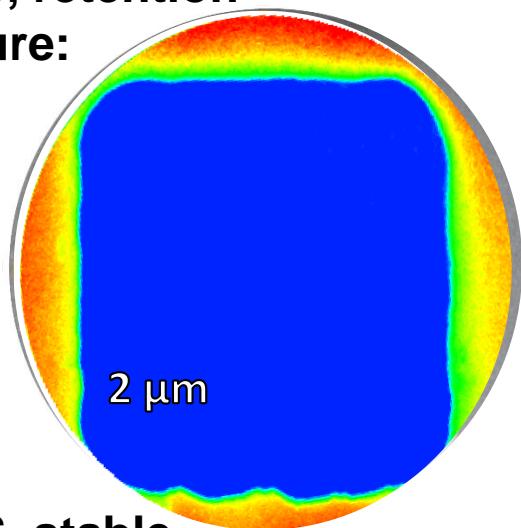


- ✓ Long retention for some devices
- ? Operation mechanism
- ? Failure mechanism
- ? Design rules

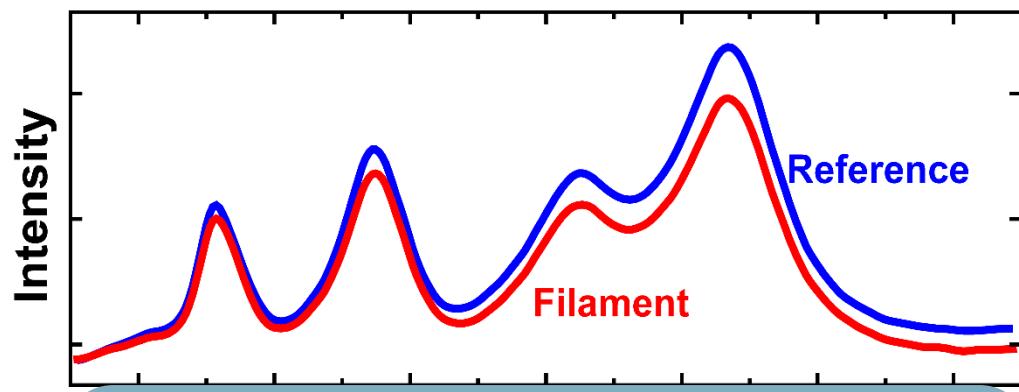
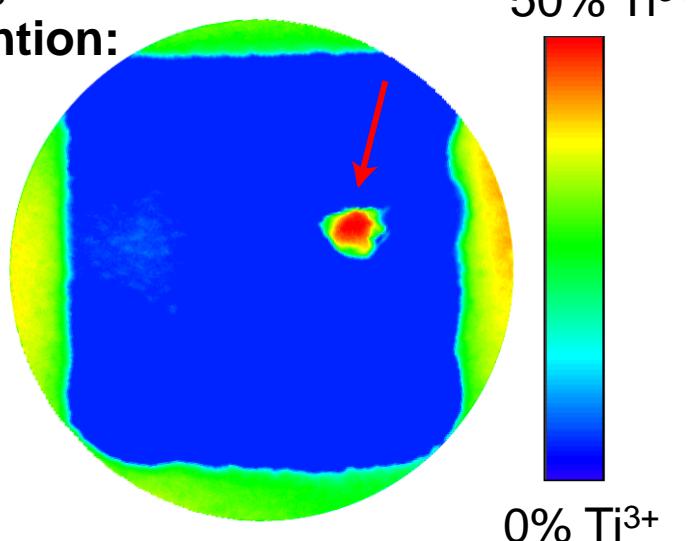


# LRS Retention Failure: Re-oxidation

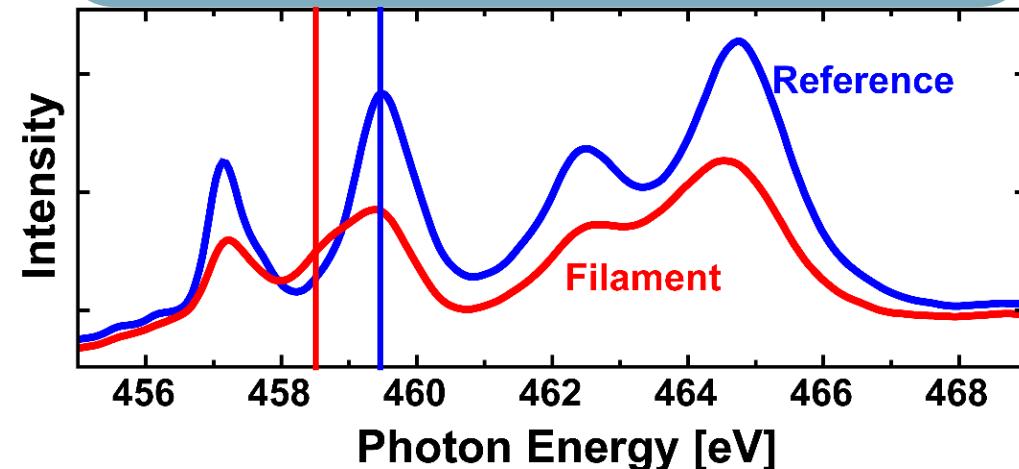
LRS, retention failure:



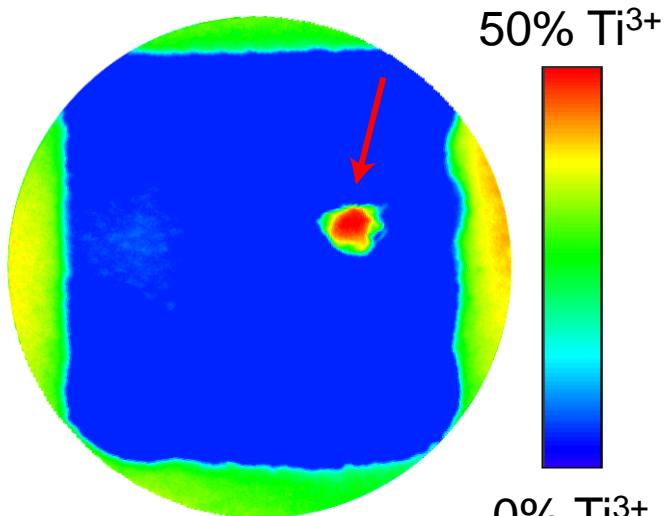
LRS, stable retention:



✓ Retention failure mechanism:  
Re-oxidation of the switching filament  
? Retention stabilization

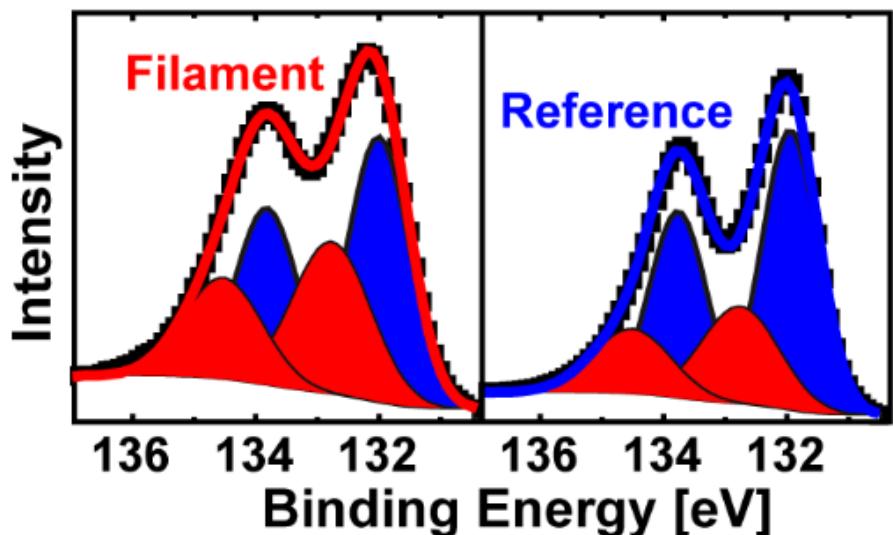
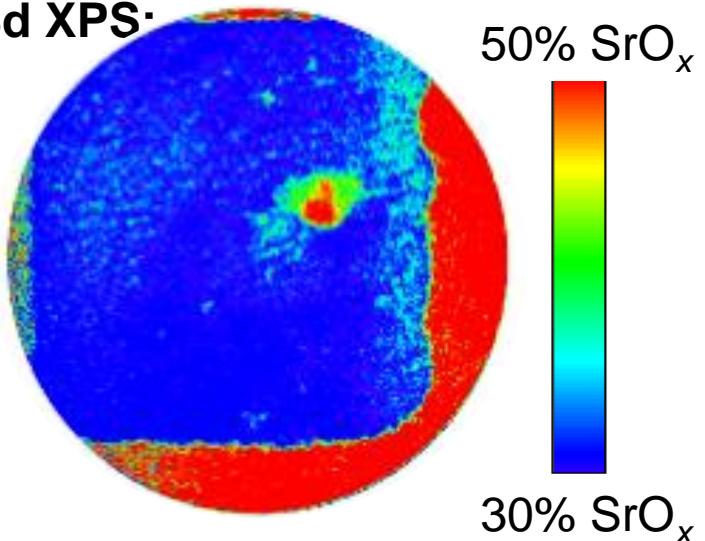


## Ti valence state:



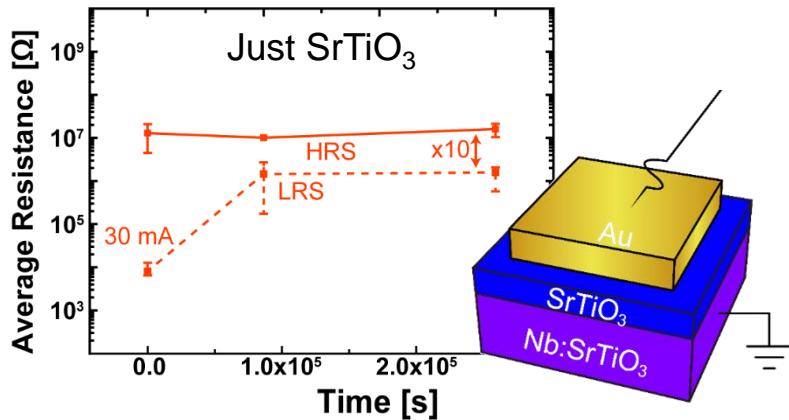
- ✓ Stable retention: Microscopic phase separation into Sr-deficient  $\text{SrTiO}_3$  and  $\text{SrO}$  surface layer
- ? Side effect or origin of retention stabilization

## Sr 3d XPS:



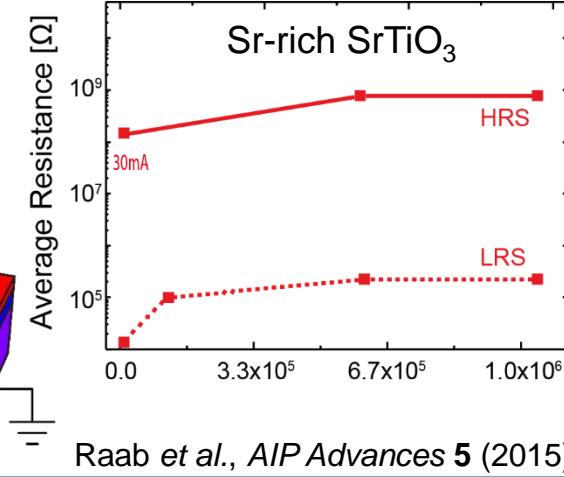
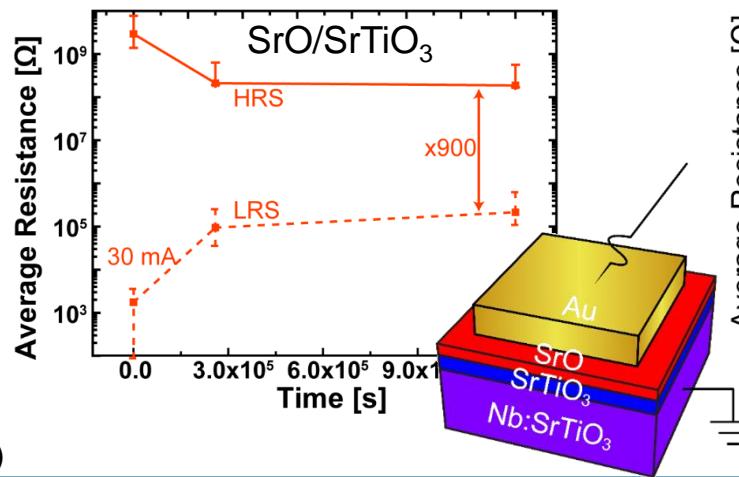
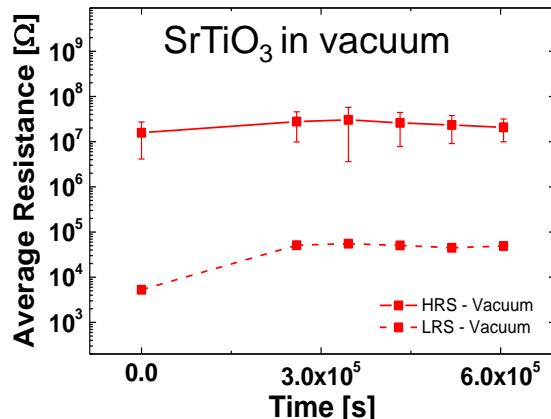
Baeumer et al., Nat. Commun. 6 (2015)

## Stoichiometric $\text{SrTiO}_3$ : Retention failure



- ✓ SrO/ $\text{SrTiO}_3$  interface inhibits re-oxidation
- ? SrO = Oxygen reservoir
- ? Role of oxygen diffusion coefficient

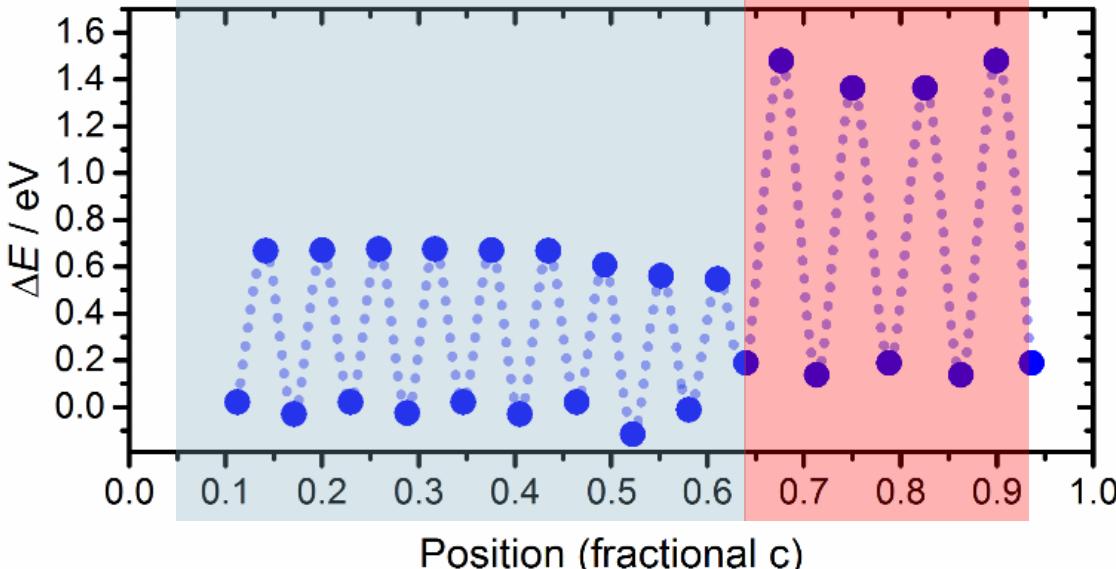
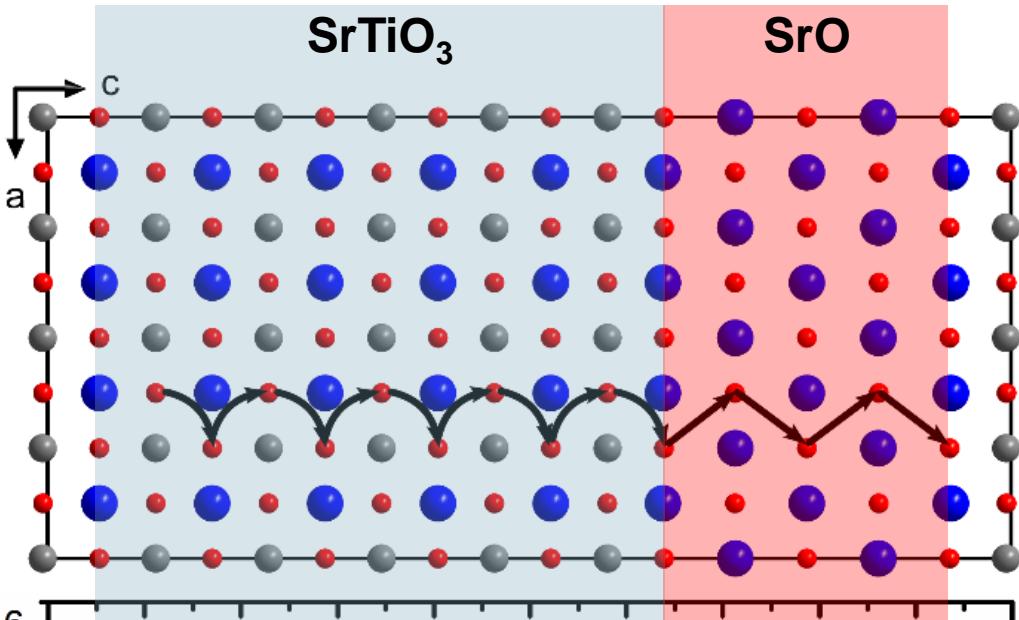
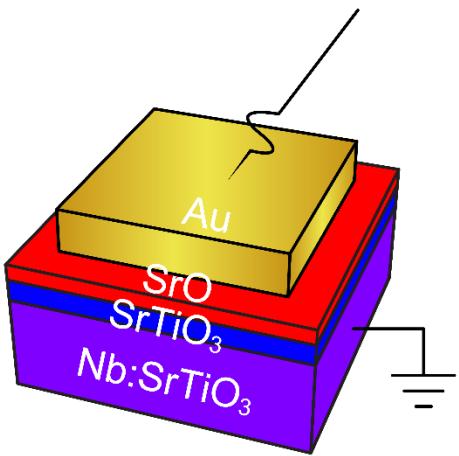
## Operation in vacuum or SrO interlayer or Sr-rich $\text{SrTiO}_3$ : Retention stabilization



Baeumer et al., Nat. Commun. 6 (2015)

Raab et al., AIP Advances 5 (2015)

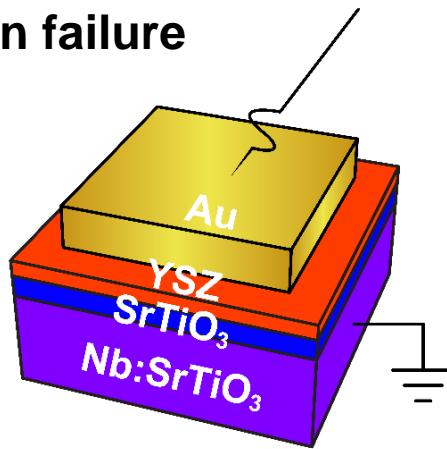
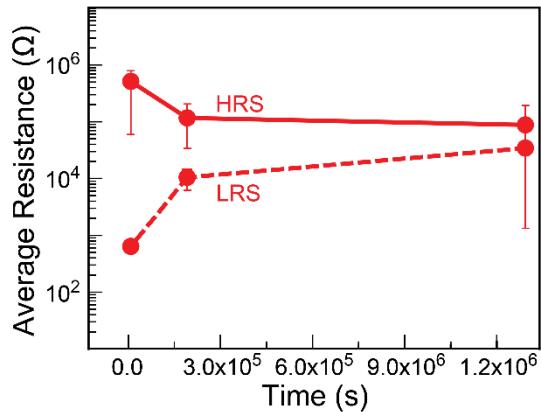
# Design Rule for Stable Retention



- ✓ SrO/SrTiO<sub>3</sub> interface inhibits re-oxidation
- ✓ Impeded oxygen diffusion in SrO

## Enhanced oxygen migration: YSZ

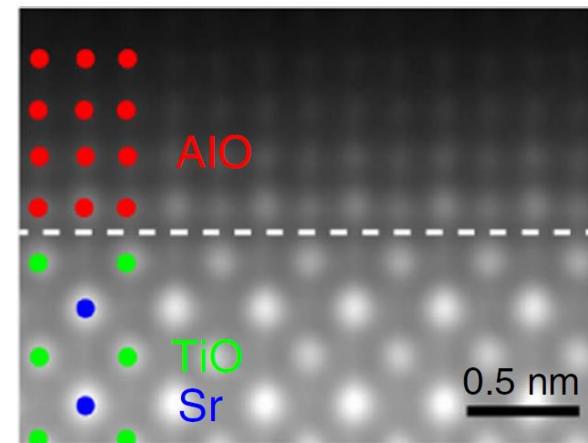
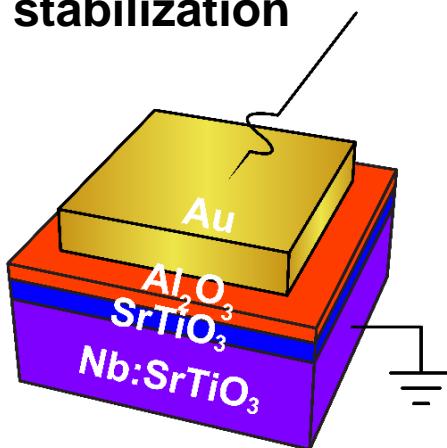
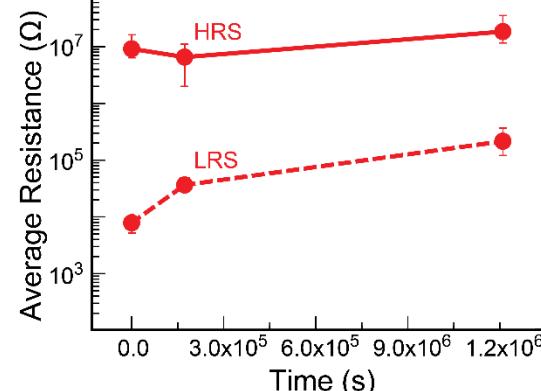
( $D(500\text{ K})=10^{-13}\text{ cm}^2\text{s}^{-1}$ ): Retention failure



- ✓ Oxygen diffusion coefficient determines retention
- ✓ Al<sub>2</sub>O<sub>3</sub> layer: good retention without structural changes

## Inhibited oxygen migration: Al<sub>2</sub>O<sub>3</sub>

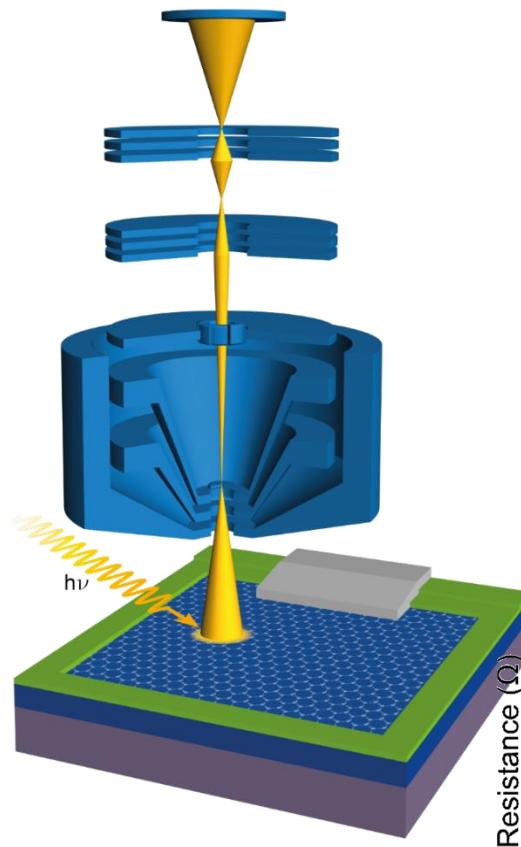
$D(500\text{ K})=10^{-65}\text{ cm}^2\text{s}^{-1}$ : Retention stabilization



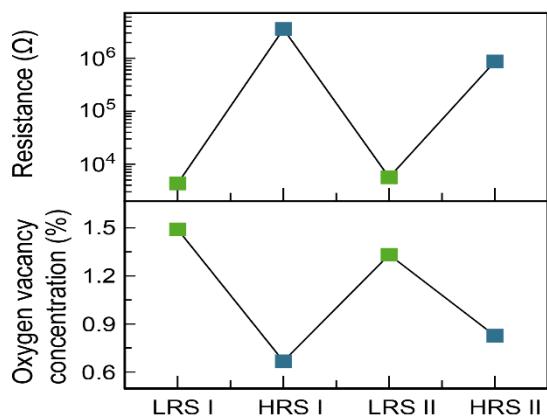
Baeumer et al., Nat. Commun. 6 (2015)

# Conclusions

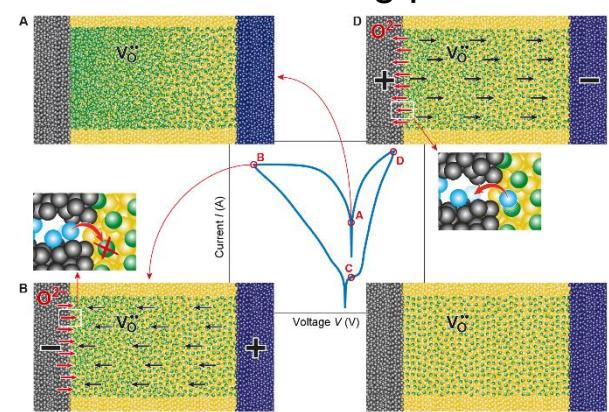
Spectromicroscopy: Post mortem & in-operando insights



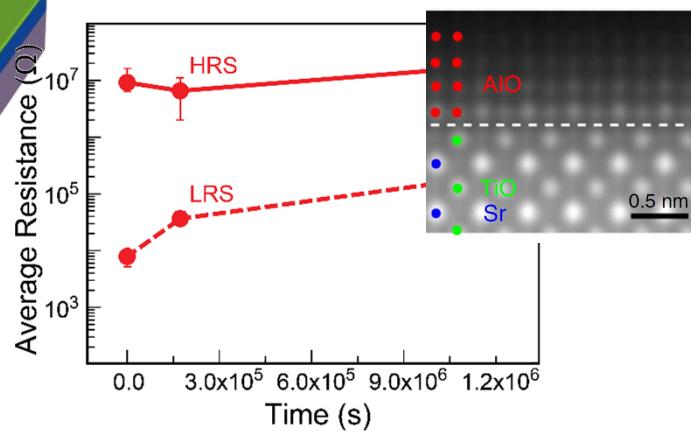
Quantitative evidence of local redox reaction



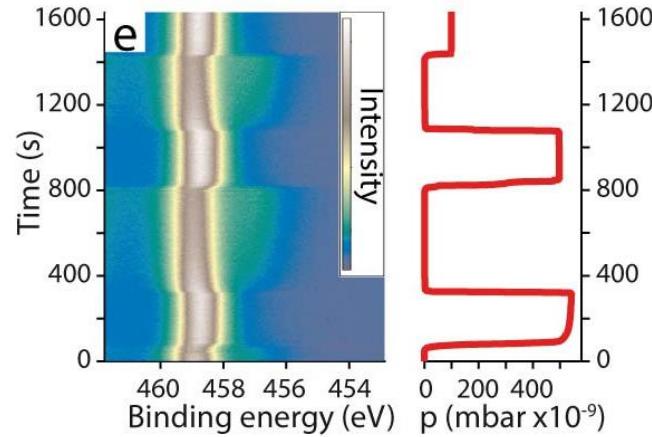
Mechanistic understanding of the switching process



Design rule: Prevent re-oxidation of filament



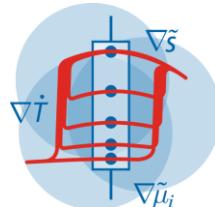
X-ray interaction: possible creation of defects (and second phases)



- Jülich: Christoph Schmitz, Nicolas Raab, Philipp Müller, Thomas Heisig, Richard Valenta, Katharina Skaja, David Müller, Stephan Menzel, Claus Michael Schneider, Ilia Valov, Rainer Waser & Regina Dittmann
- CEA/LETI: David Cooper
- Bessy: Imtiaz Khan, Johanna Hackl & Slavomir Nemsak
- Elettra: Vitaliy Feyer, Andrea Locatelli, Tevfik Onur Mentes
- RWTH: Camilla La Torre, Astrid Marchewka & Stephan Menzel
- UIUC: Steven Rogers & Moonsub Shim

# Thank you for your attention!

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